

Mechanisms of cavity formation in GaN devices induced by swift heavy ion irradiation

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2024 AFRL Radiation Damage of Electronics Review
AFOSR MURI: REDESIGN



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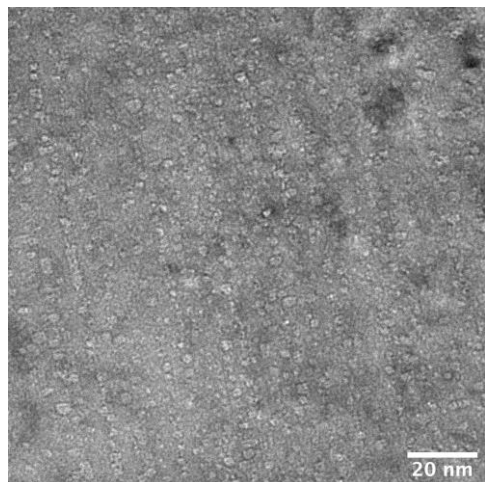


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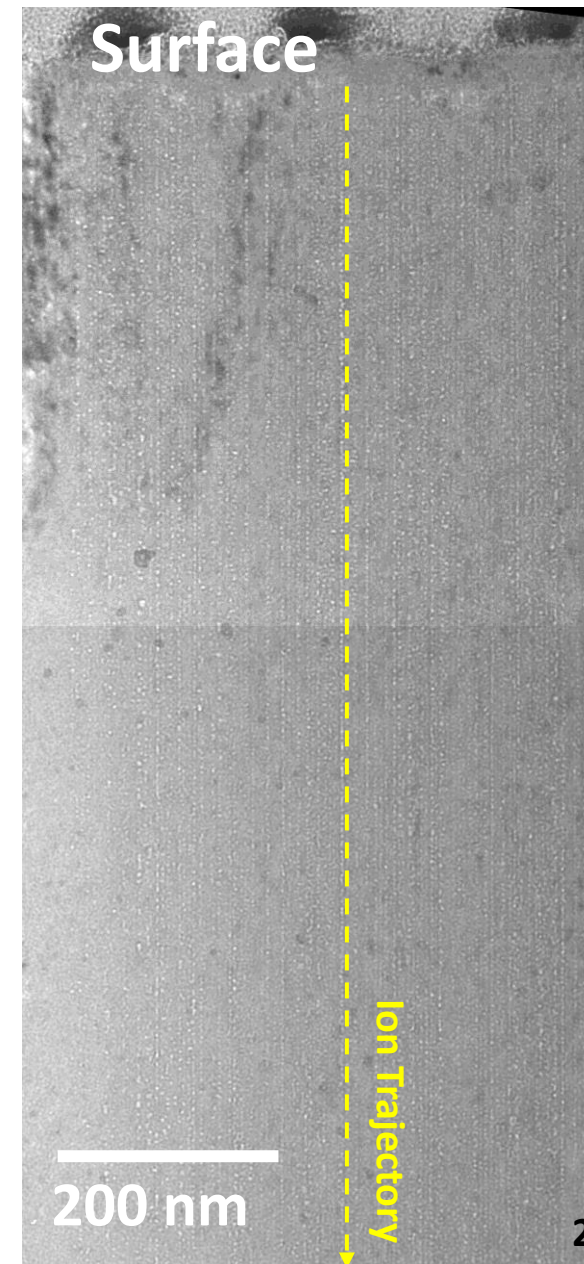
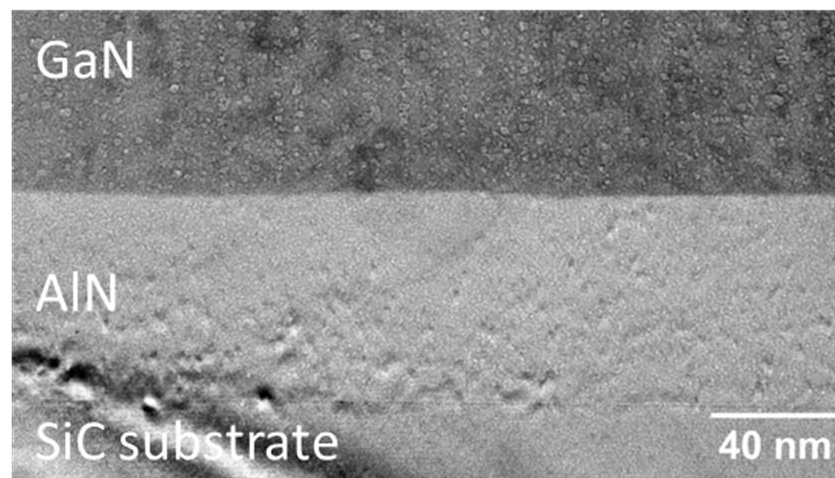
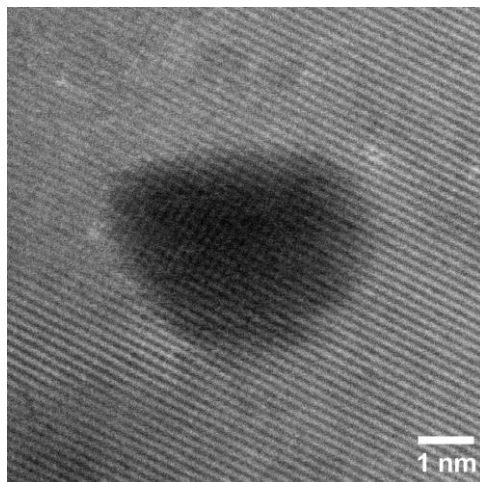
Background

- **Swift Heavy Ions:** $Z > 6$, Ion Energy $> \text{MeV/amu}$
- Lower fluence than lighter ions but substantial damage
- 950 MeV Au ions irradiation with fluence $\sim 10^{12} \text{ cm}^{-2}$ in GaN
 - *Dense nano-sized cavities formed in GaN*
 - *Cavities formed along the Au ion trajectory, indicating the effect of single ion on cavity formation*
 - *Much smaller cavities in AlN than GaN*

Under-focused TEM



STEM-HAADF



Mechanisms for cavity formation remains unclear

- Why cavities only formed at high LET (> 40 keV/nm)?
- Cavity: voids or N_2 gas bubbles?
- What is the impact of Al in Al_xGaN on cavity formation?

Microscopy Characterization

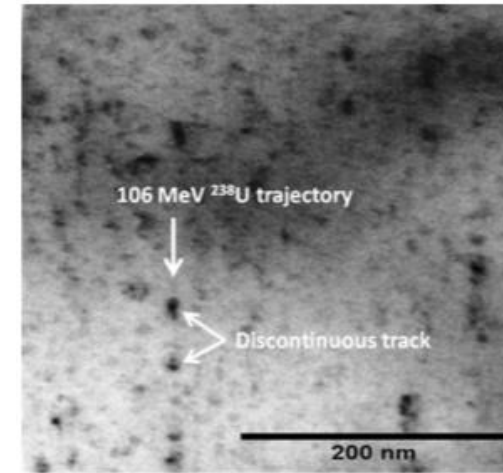
Nitrogen Measurement
by EELS

Element Segregation
by Atom Probe

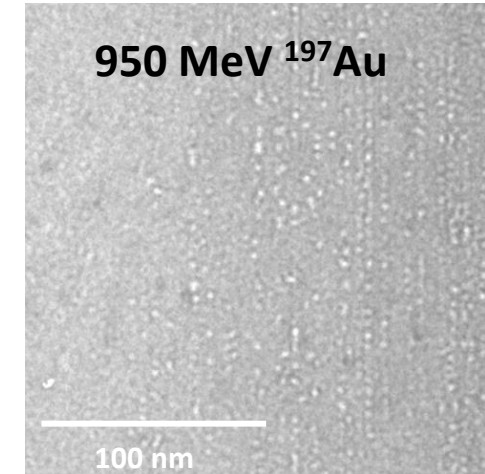
Role of Al using
Multilayer Samples

Mechanisms for
Cavity Formation

Understanding
Behavior of GaN
and Devices at
Lower Fluence



LET = 24 keV/nm [1,2]



LET = 46 keV/nm

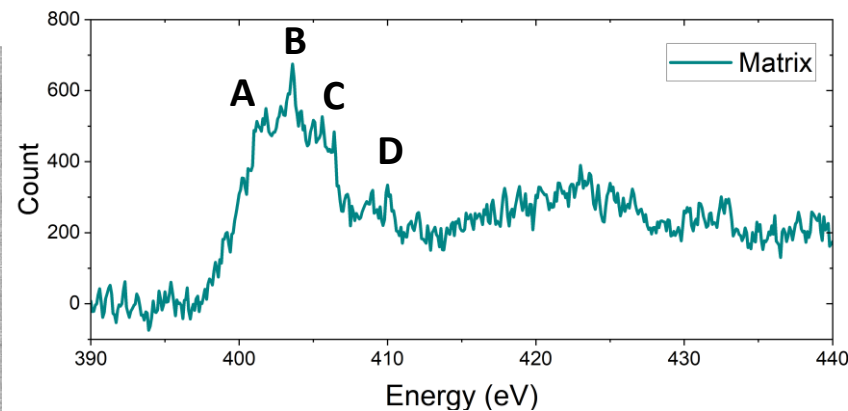
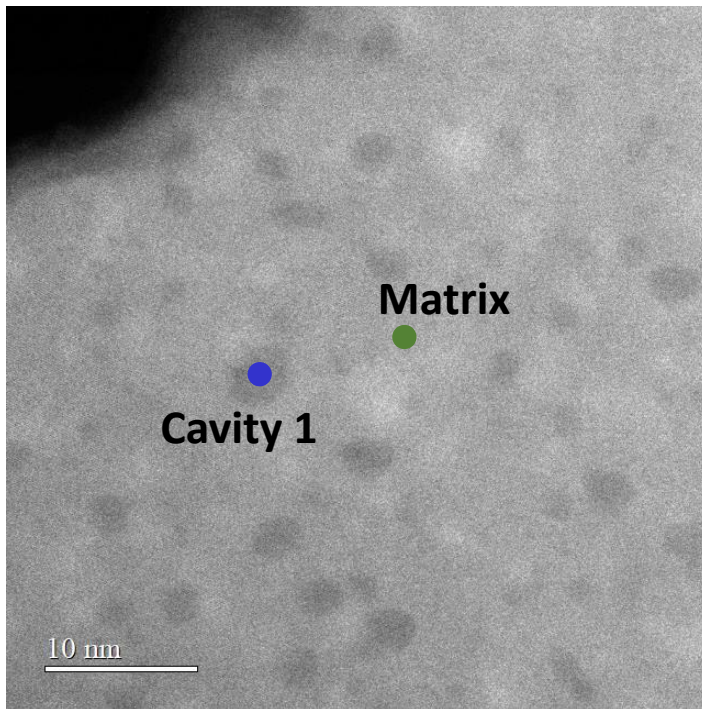
[1] M. Sall, I. Monnet, et al., J. Mater. Sci. **50**, 5214 (2015).

[2] M. C. Sequeira, et al., Small **18**, (2022).

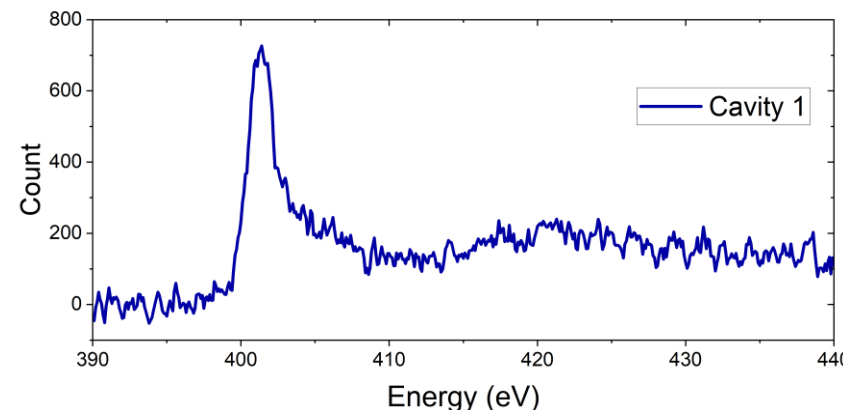
Nitrogen Measurement using Electron Energy Loss Spectroscopy (EELS)

Why EELS?

- More sensitive for lighter elements, like N, C, O, than EDS
- Fine features near core-loss peaks can reveal bonding environment, as it is related to density of states of unoccupied electronic orbitals
- Measurement of relative element concentration with careful data processing



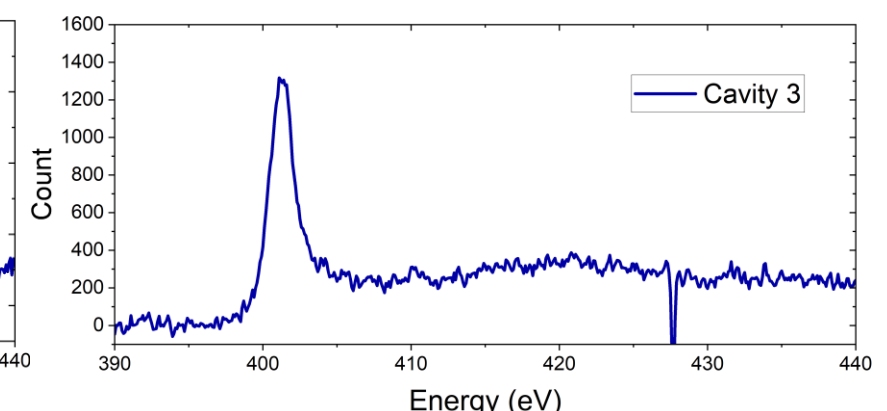
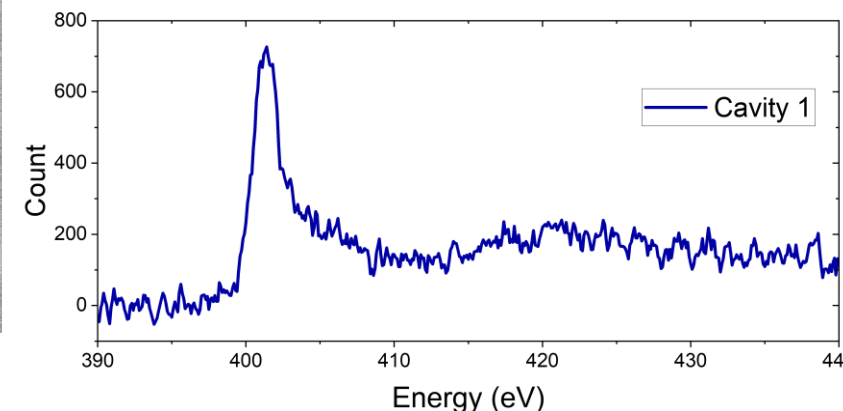
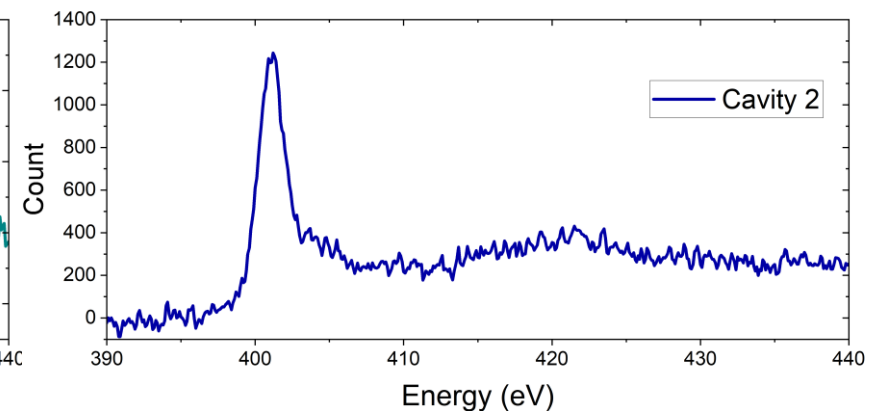
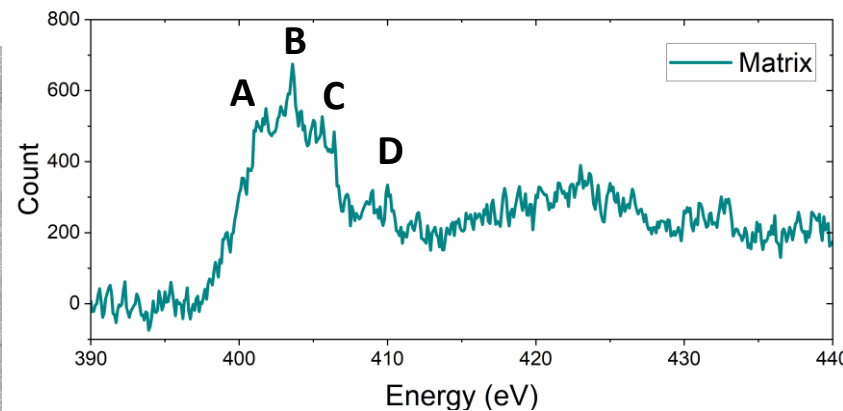
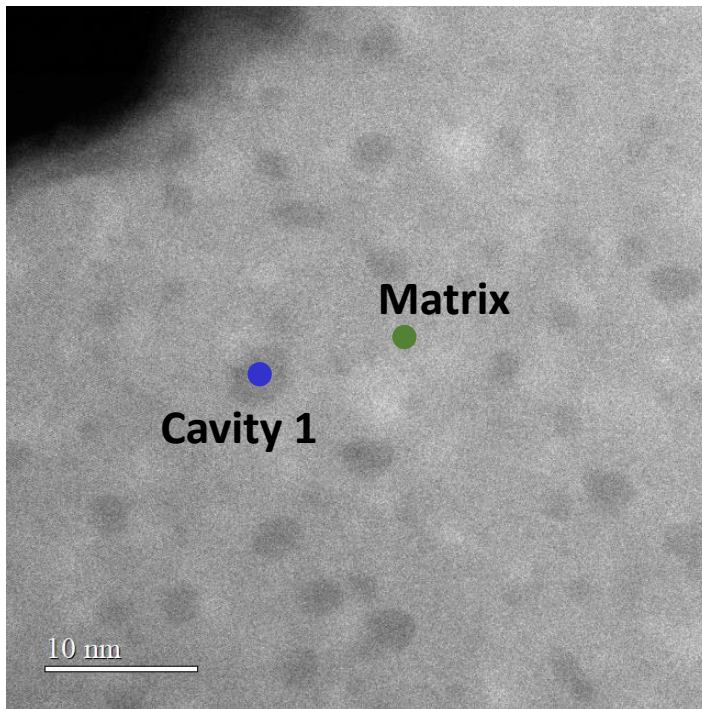
A peak: hybridization between all electrons
B peak: hybridization of Ga s and N p in x-y plane
C peak: hybridization of p states
D peak: hybridization of Ga p and N p_x , p_y



Nitrogen Measurement using Electron Energy Loss Spectroscopy (EELS)

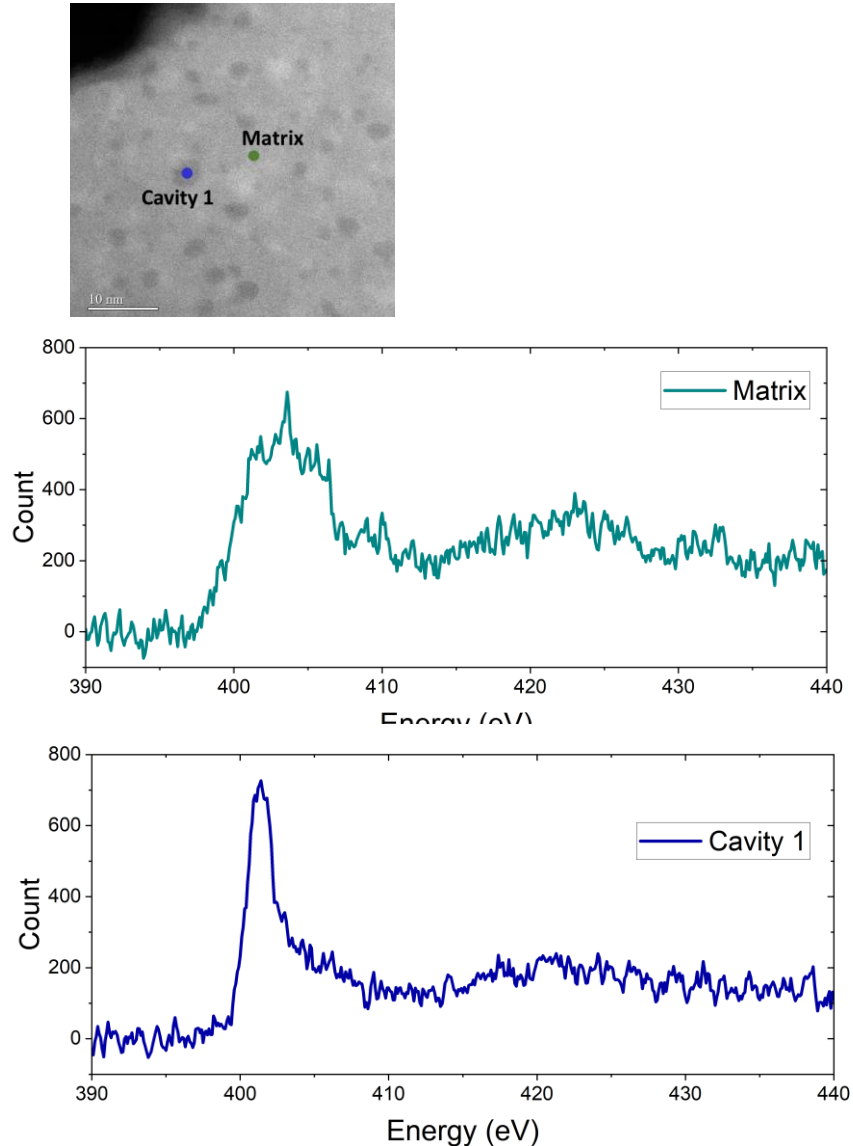
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Nitrogen Measurement using Electron Energy Loss Spectroscopy (EELS)

- GaN irradiated by 950 MeV Au

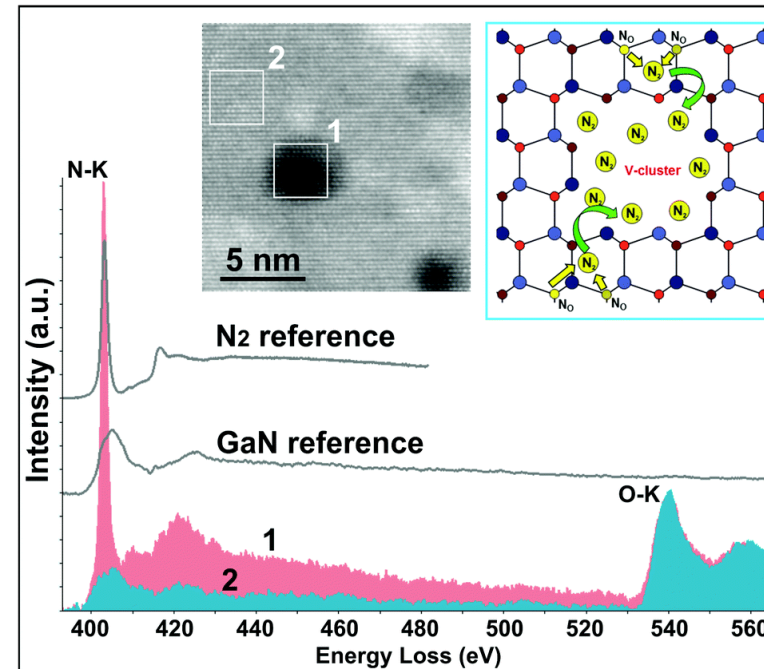
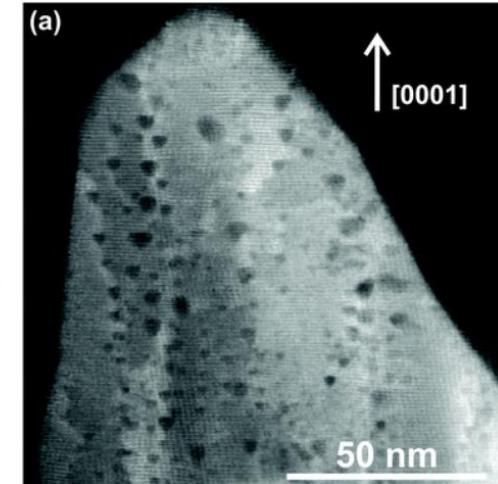
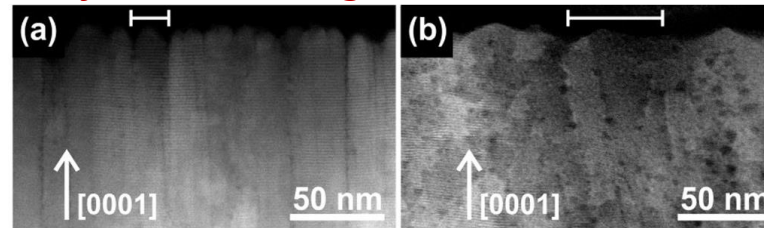


- Annealing of $(\text{ZnO})_{1-x}(\text{GaN})_x$ thin film

C. Bazioti, V.S. Olsen, A.Y. Kuznetsov, L. Vines, Ø. Prytz, *Phys. Chem. Chem. Phys.* 22 (2020), 3779.

- Magnetron sputtering to form thin film
- Annealing under N_2 environment at 800C for 1hr

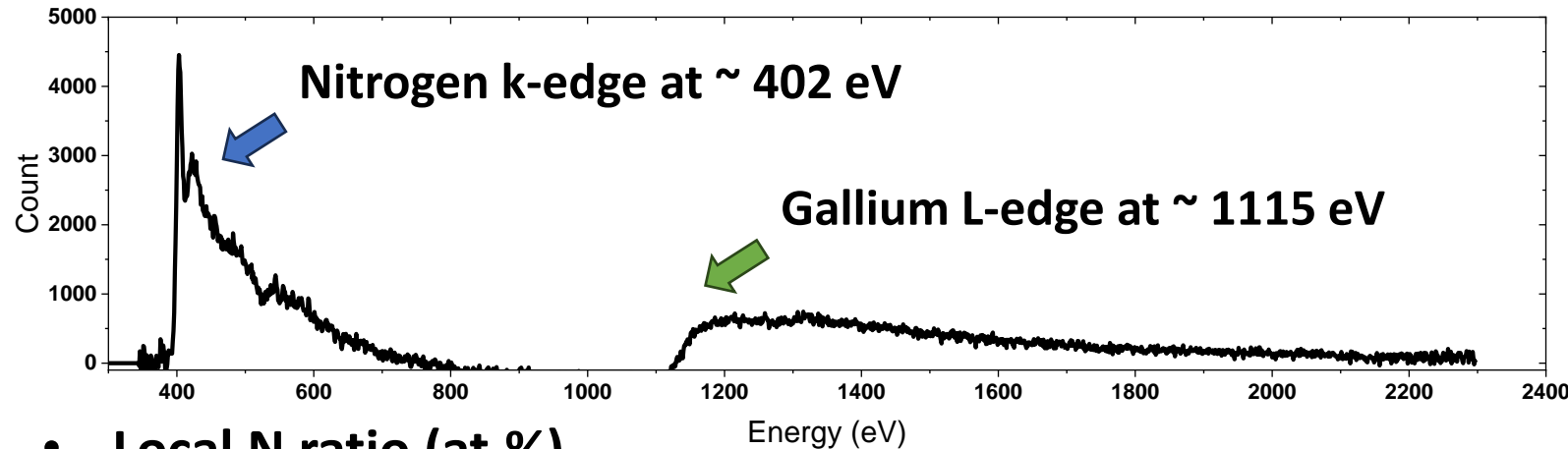
Before annealing *After annealing*



- Cavities formed near grain boundaries

Nitrogen Measurement using Electron Energy Loss Spectroscopy (EELS)

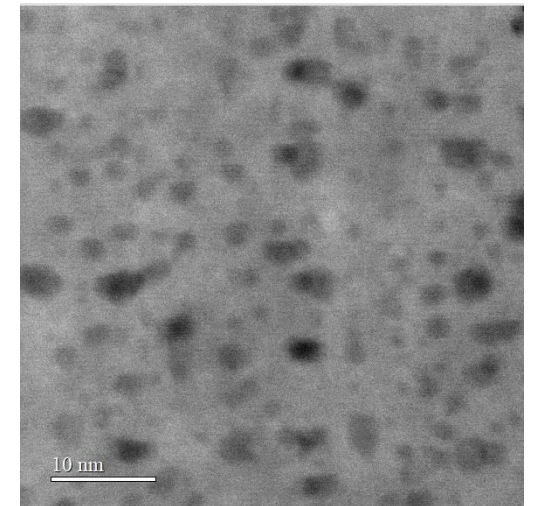
- Wider EELS for measuring local N to Ga ratio



$$\frac{N \text{ conc.}}{Ga \text{ conc.}} = \frac{N \text{ peak counts} \times \sigma_{Ga}}{Ga \text{ peak counts} \times \sigma_N}$$

- Local N ratio (at.%)

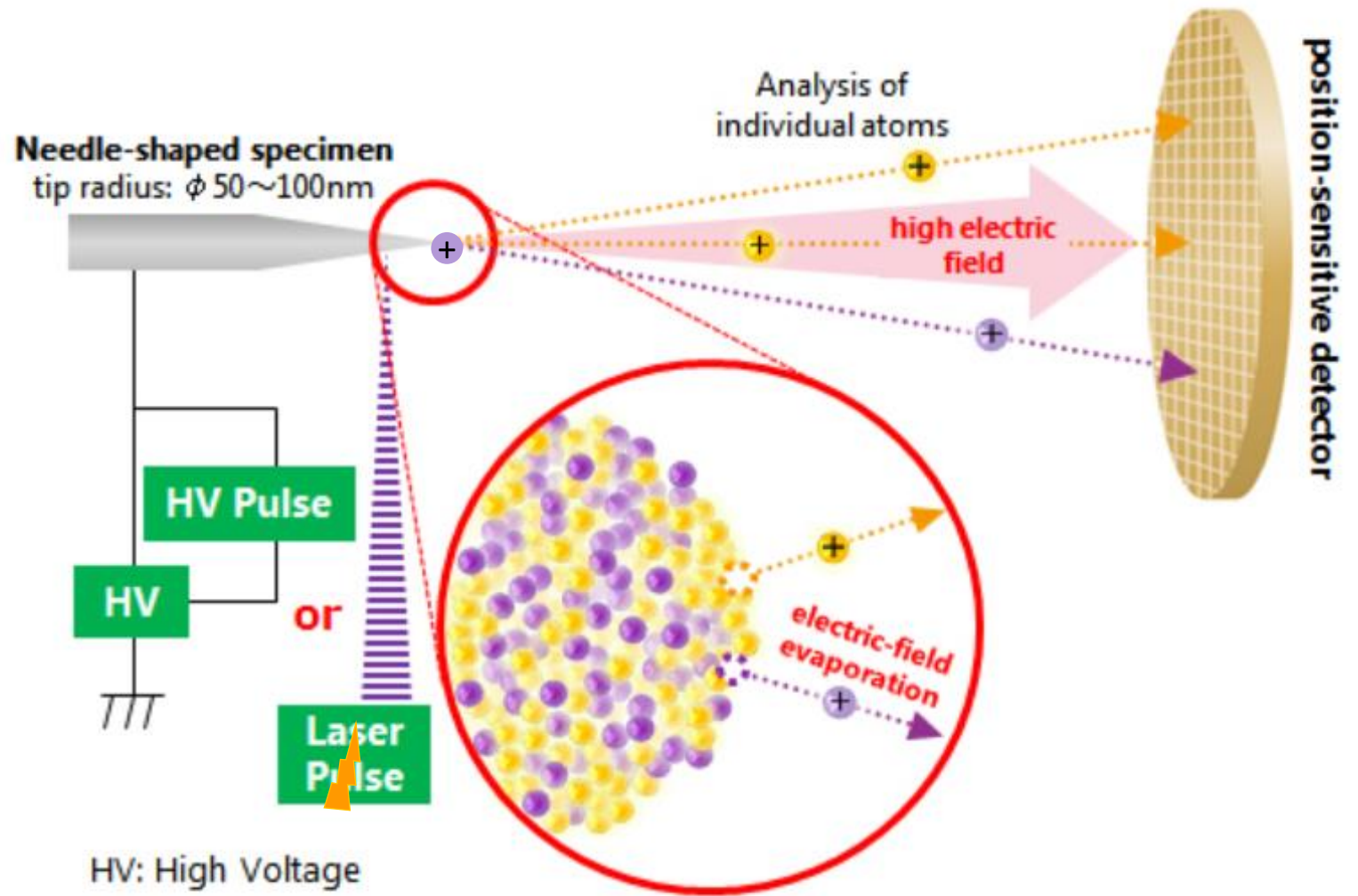
Measure.	1	2	3	4	5	6	Ave.
Cavities	37.1	43.5	37.5	39	36.2	36.5	38.3±2.5
Matrix	31.8	31.7	33.3	32	30.9	32	32.0±0.7



- Potential EELS signals of N₂ were detected inside the cavities
- Cavities are slightly more enriched in nitrogen than matrix
- **Potential Issues & Limitation**
 - Beam damage from 300 keV electron used in STEM → will use 80 kV STEM
 - Effects of sample thickness on EELS background → will prepare thinner samples for EELS
 - Nanosized cavities are buried inside the TEM foil → averaging effect

3D Segregation near Cavities – Atom Probe Tomography (APT) Characterization

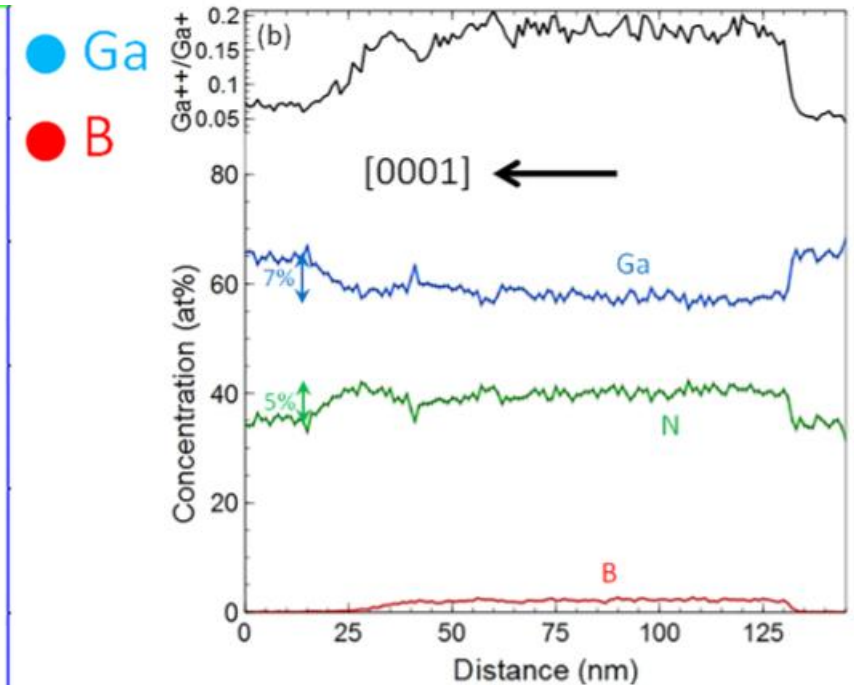
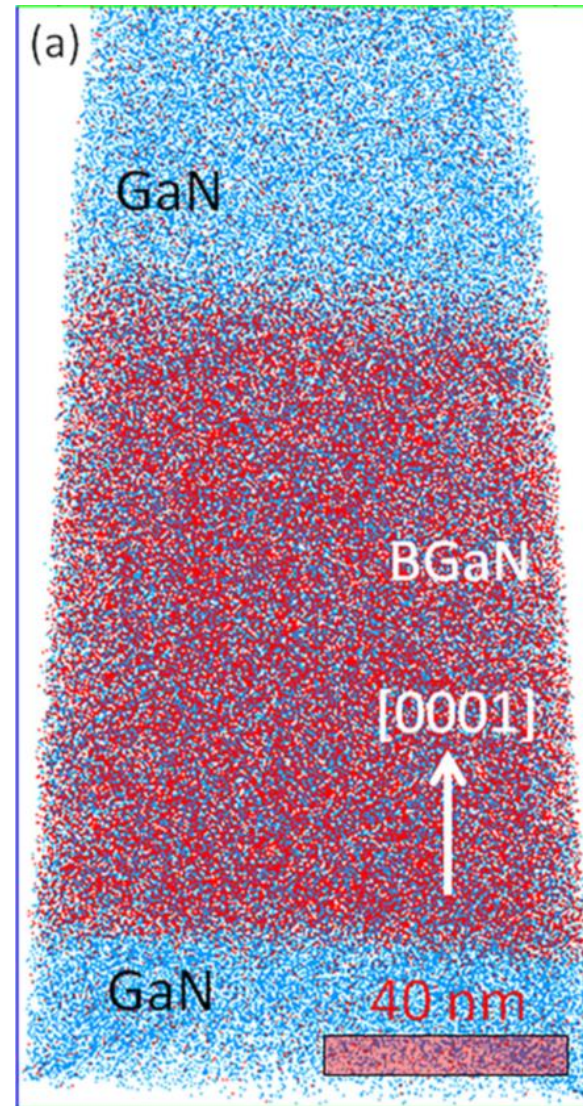
- APT: identify materials' composition atom-by-atom
- High sensitivity for most elements and isotopes (<10 ppm)
→ no averaging effect
- 3D reconstruction of atom positions and element type
→ no averaging effect
- APT sample temperature:
30-50 K (< N₂ melting point 63.15K)



The basic principle of APT

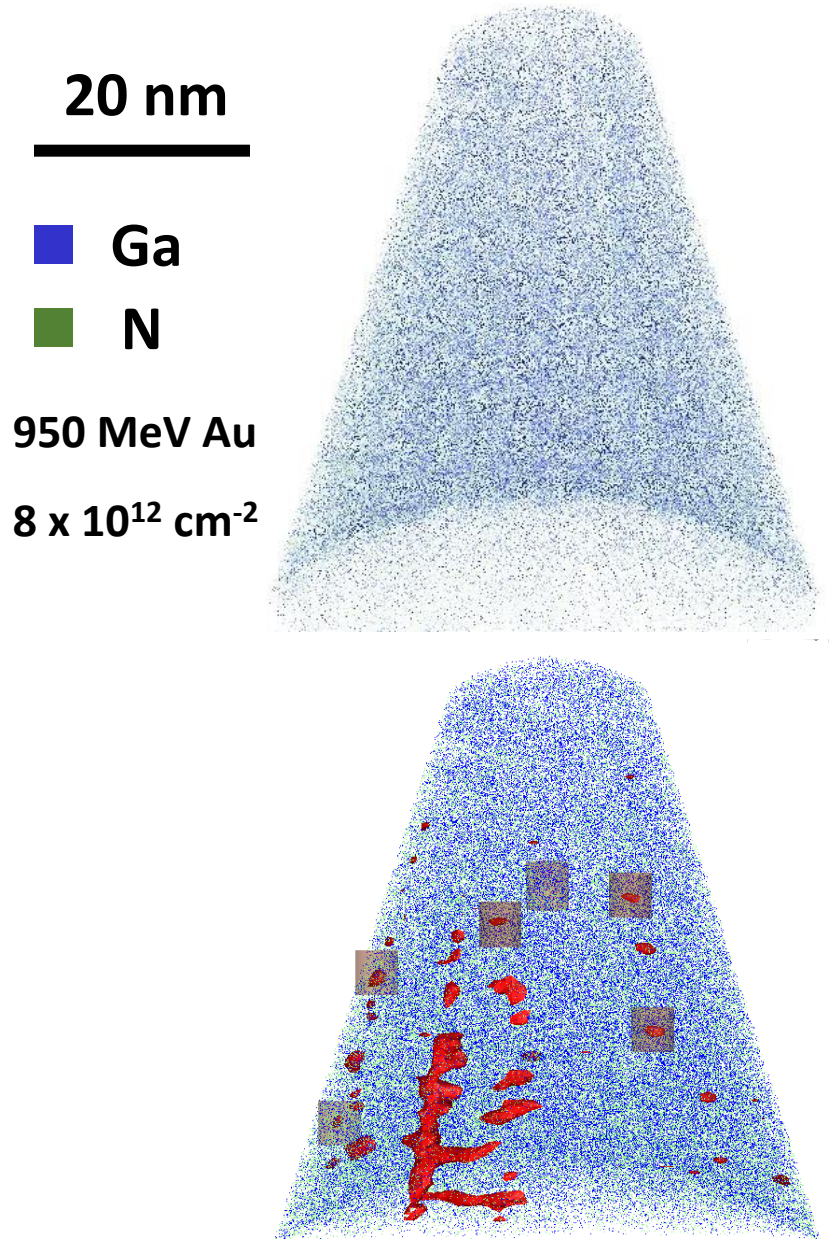
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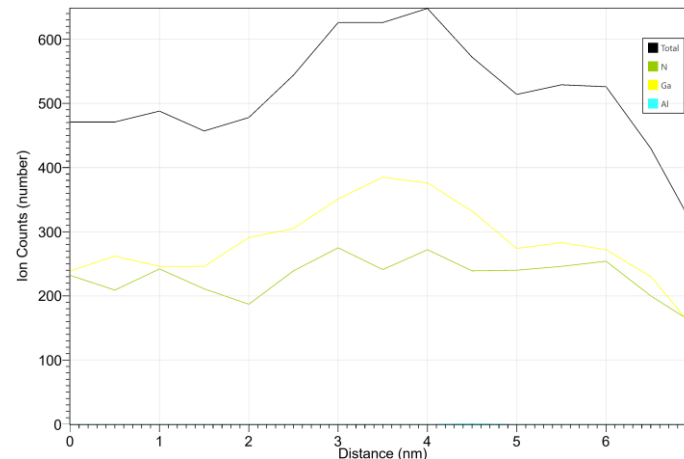


B. Bonef, R. Cramer, J.S. Speck, Nanometer scale composition study of MBE grown BGaN performed by atom probe tomography, J Appl Phys 121 (2017).

3D Segregation near Cavities – Atom Probe Tomography (APT) characterization



- No nitrogen-rich region could be detected
- Potential reasons: (1) N_2 may quickly evaporate under laser pulse even at 30 K; (2) Low N_2 concentration inside cavities
- If GaN dissociates, Ga-rich rims should form around cavities
- Multiple local regions showing slight Ga enrichment
- More APT with better controlled parameters (tip temperature, laser energy, etc.) will be conducted

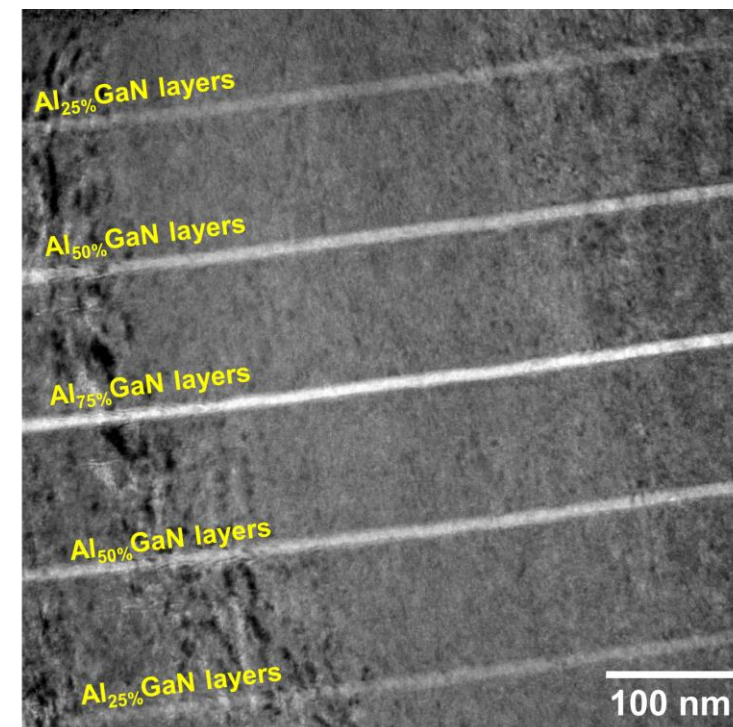
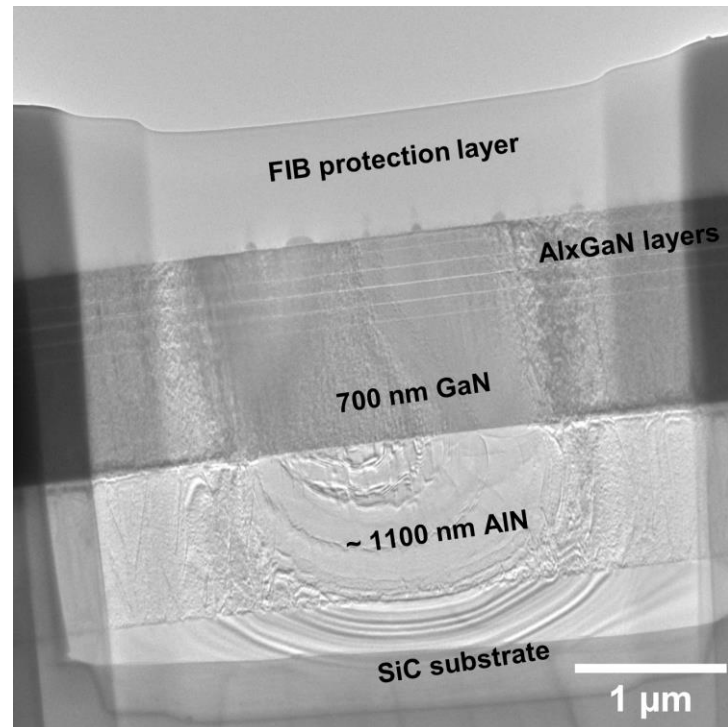


Total Cavities	Ga-rich	N-rich
15	14	1

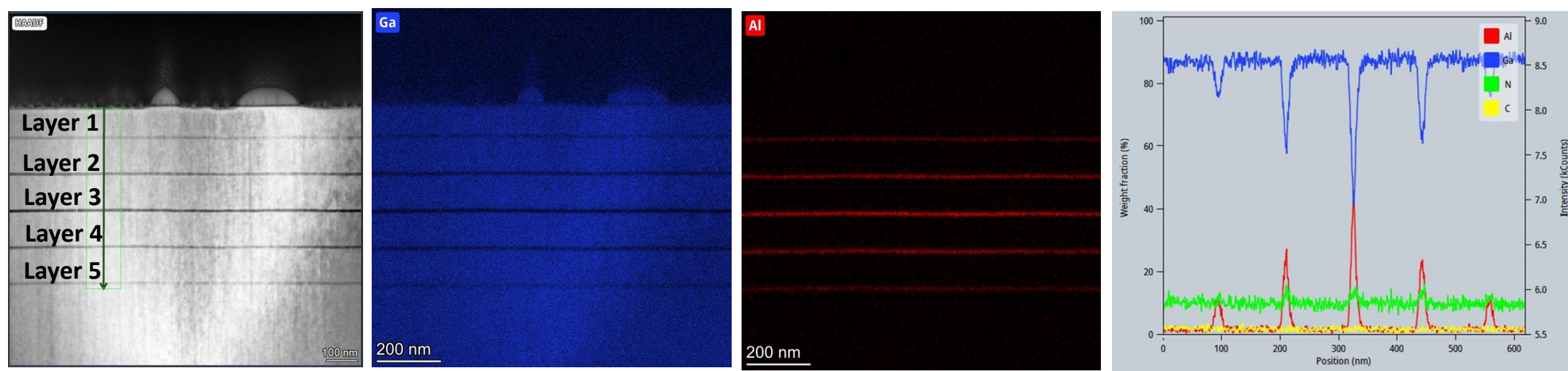
Impact of Al concentration on cavity formation

- Multilayered sample fabricated by AFRL and irradiated by Prof. Maik Lang at UTK
- 950 MeV Au ion; two different fluences; room temperature

Sample	Pristine	Low-fluence	High-fluence
Fluence (ions/cm ²)	0	3e11	8e12



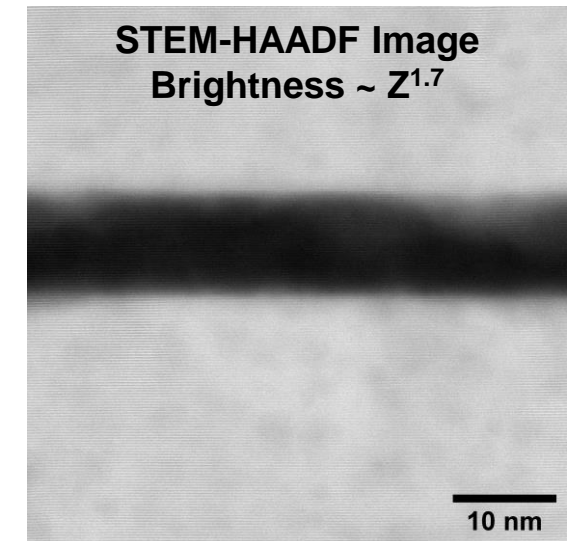
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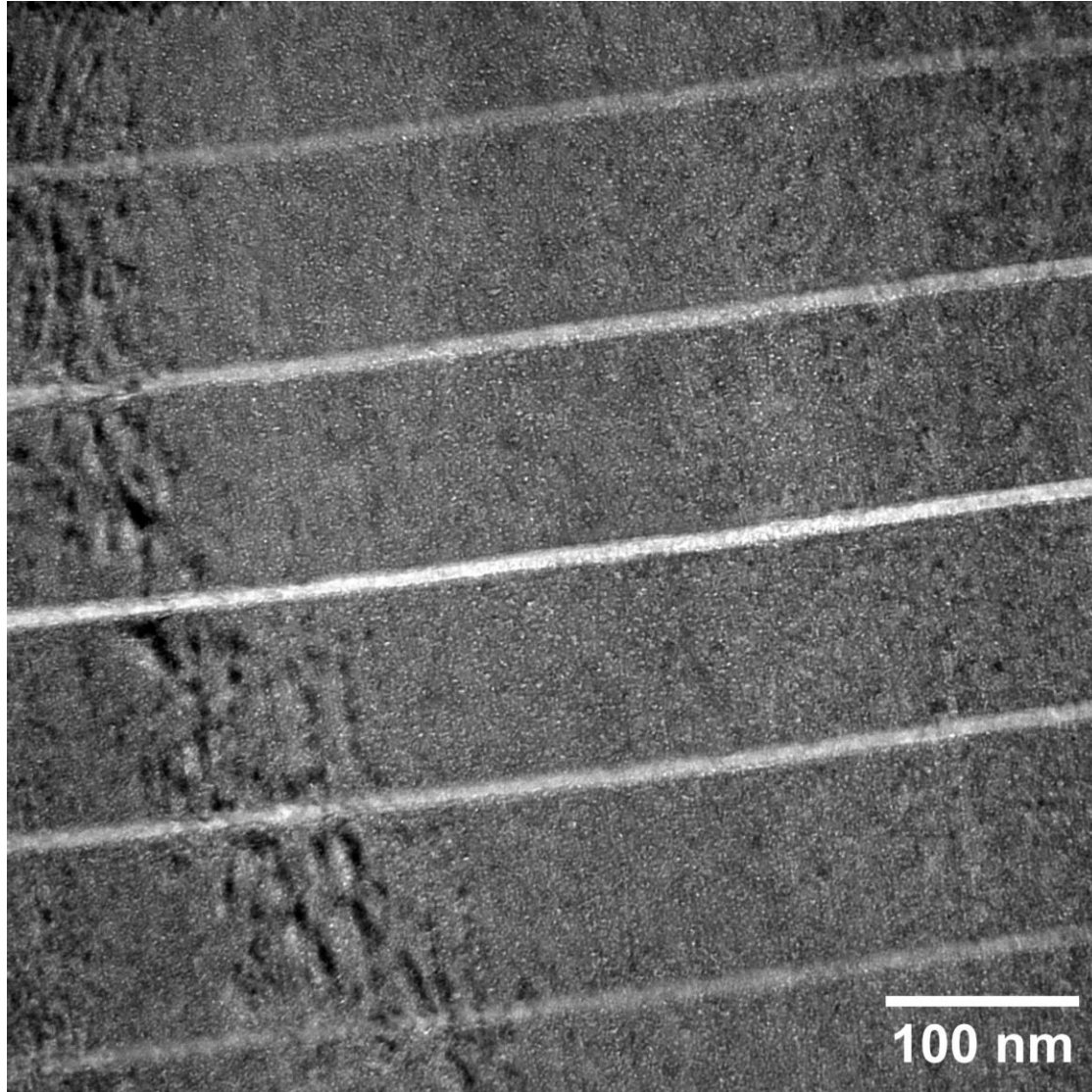
- **Al concentration: Layer 3 > Layer 2 or 4 > Layer 1 or 5**
- **More accurate composition measurement using RBS (from Prof. Maik Lang)**

Layer 1	Layer 2	Layer 3	Layer 4	Layer 5
17% Al	26.5%	37.5%	25.5%	26.5%

- **Element intermixing occurs between layers, likely due to fabrication & irradiation**



Under-focused TEM images

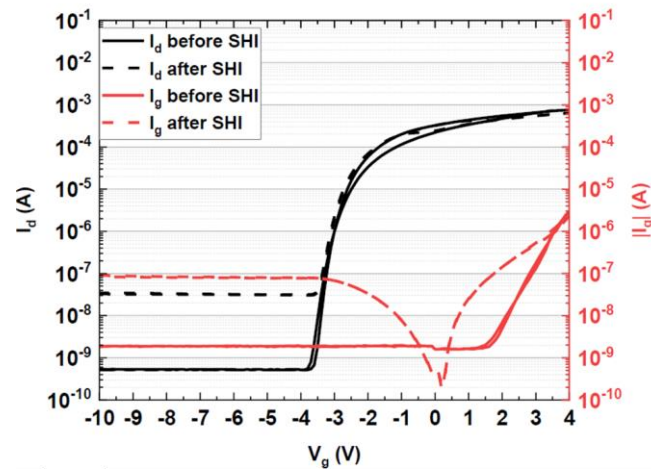
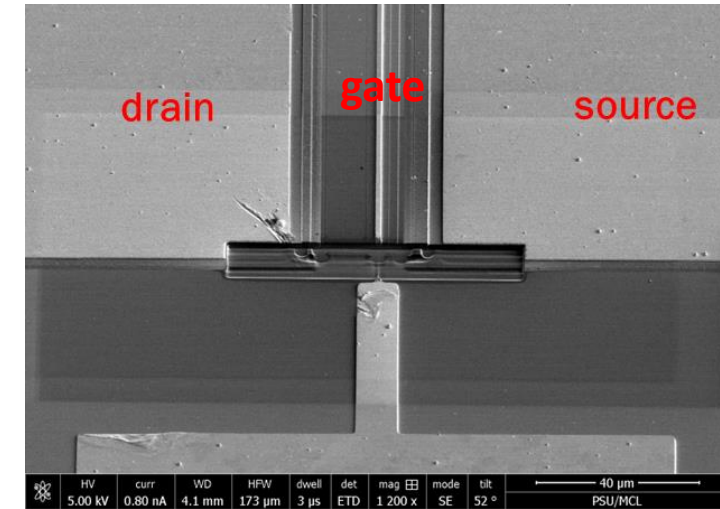
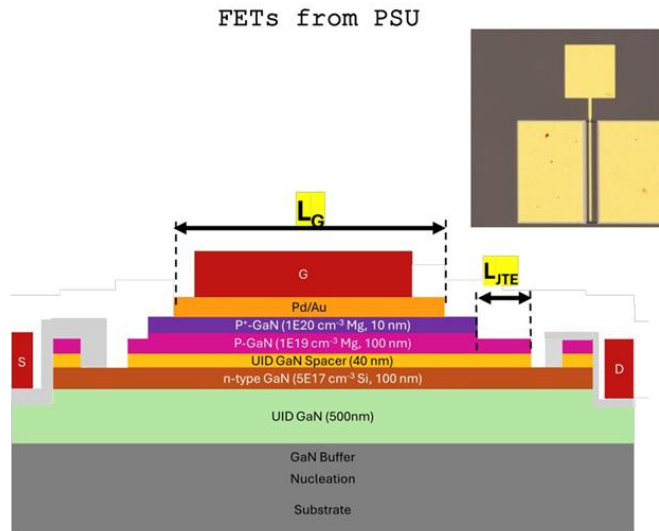


- Cavity formation is reduced as Al concentration increases
- Results consistent with MD simulations
- Element intermixing at interfaces may cause cavity formation near Layer 3
- Analysis of similar samples with thick layers in collaboration with Prof. Reeja Jayan from CMU

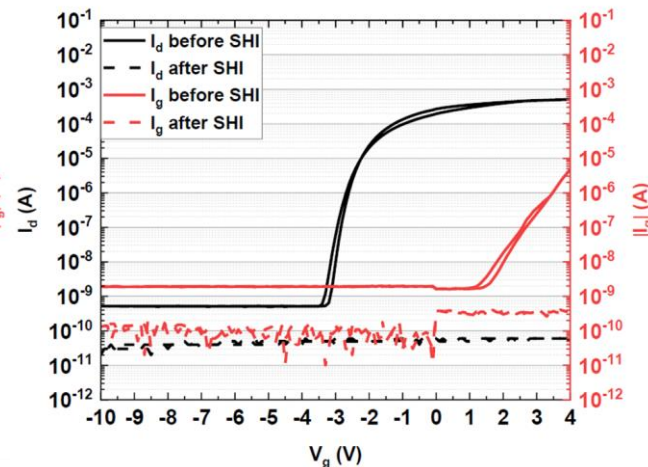
	Ave. cavity diameter (nm)	Cavity density (1/nm ²)
Layer 1	1.3	0.075
Layer 2	1.7	0.044
Layer 3	1.4	0.024

Impact of Cavities on GaN Properties and Device Performance

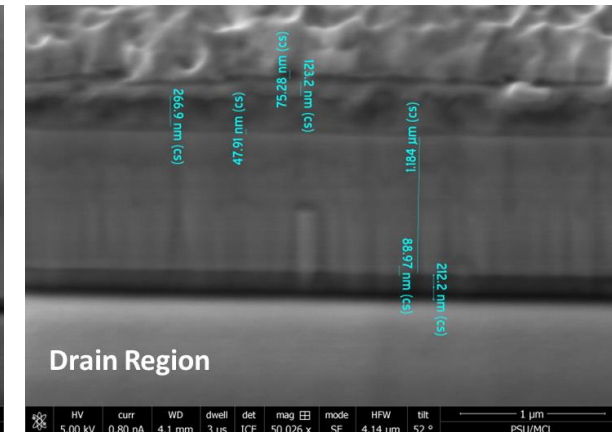
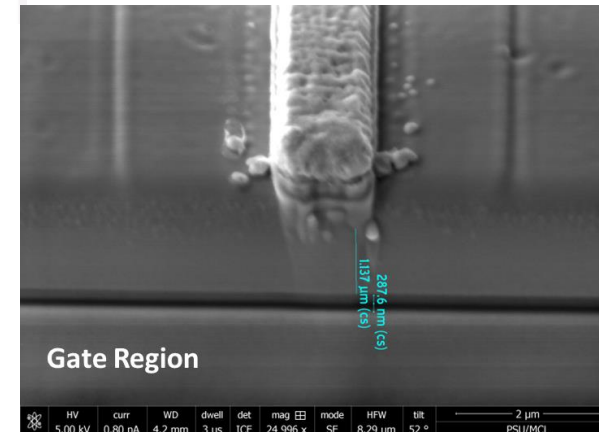
- 950 MeV Au ion
- Room temperature irradiation
- Two difference fluences: $1 \times 10^7 \text{ ions/cm}^2$ and $5 \times 10^{11} \text{ ions/cm}^2$



$1 \times 10^7 \text{ ions/cm}^2$



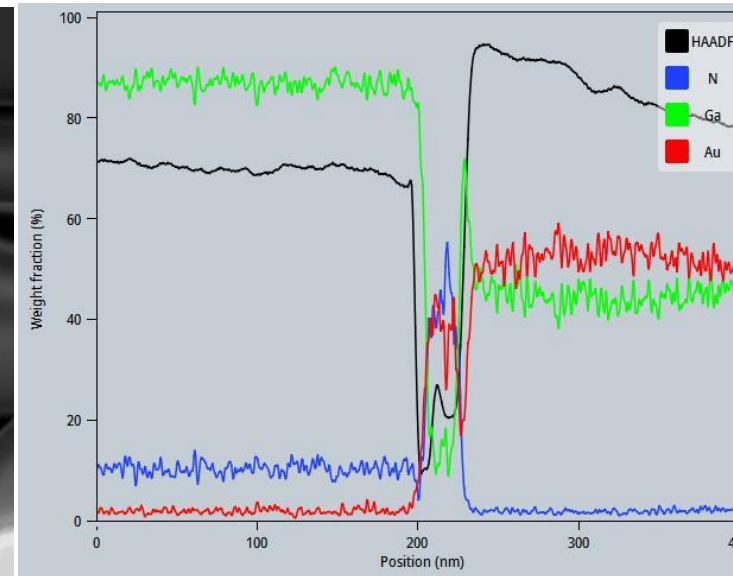
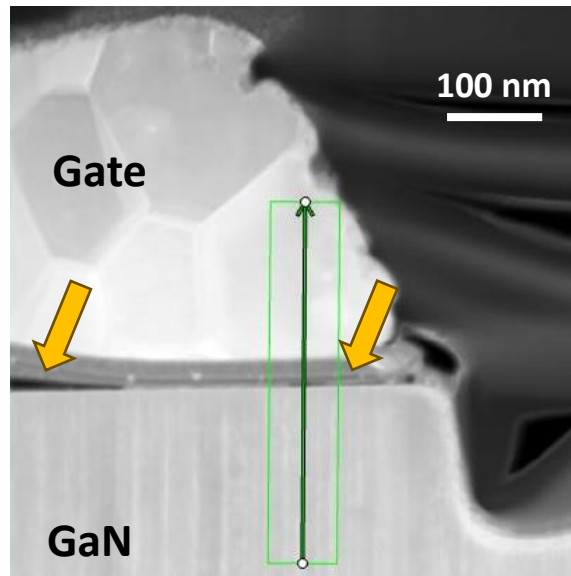
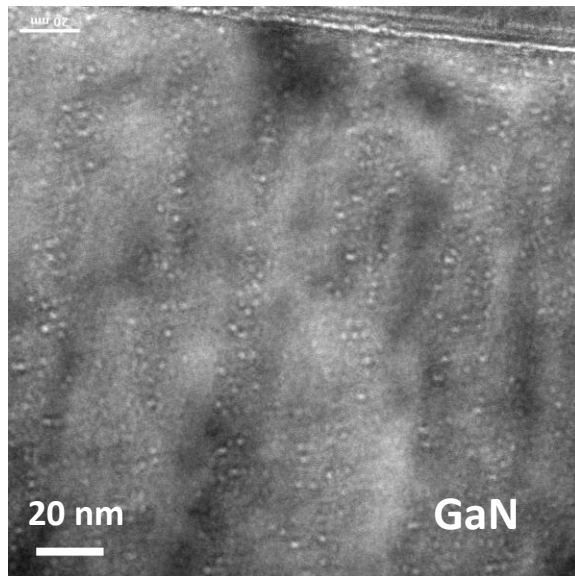
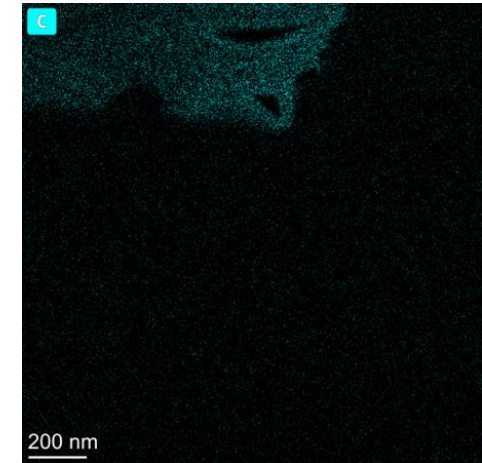
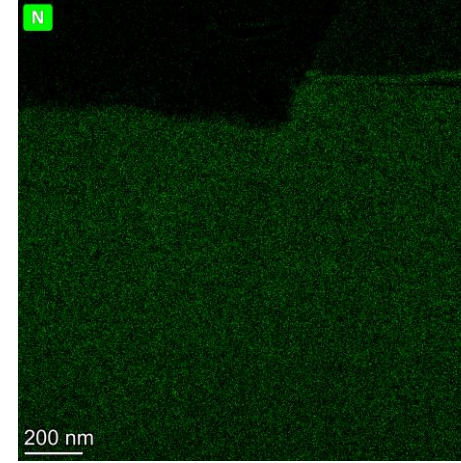
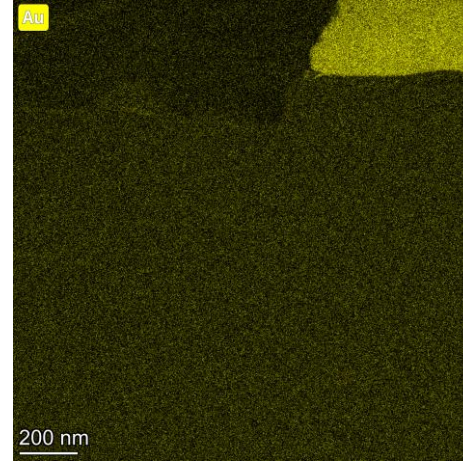
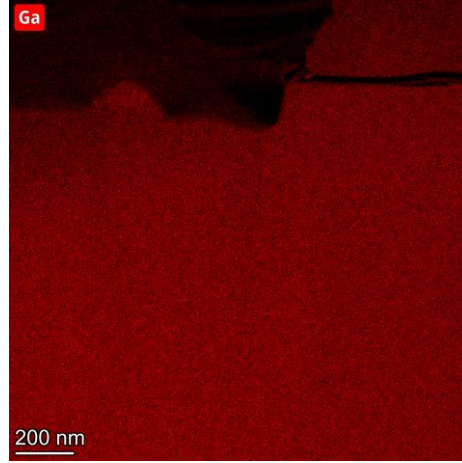
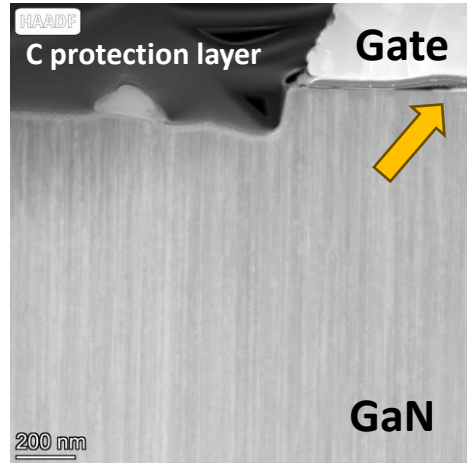
$5 \times 10^{11} \text{ ions/cm}^2$



- Despite high ion fluence and device failure, no delamination can be found using FIB-SEM

Device testing results from Prof. Chu's group

Impact of Cavities on GaN Properties and Device Performance – TEM analysis



- Dense nano-sized cavities in GaN
- Gaps between gate and GaN
- A layer of different composition between GaN and gold gate

Conclusions

- Potential EELS signals of N₂ were detected inside the cavities; Cavities are slightly more enriched in nitrogen than matrix → Potential GaN dissociation under SHI irradiation
- APT did not observe nitrogen-rich regions
- As aluminum concentration increases in Al_xGaN, the cavity density decreases, which is consistent with MD simulation

Future Work

- Analysis of low-fluence samples (1E10-1E11 ions/cm²) to identify single track effect, *in collaboration with Dr. Maik Lang and AFRL*
- Role of N₂ and Al concentration in cavity formation, *in collaboration with Dr. Mia Jin at Penn State*
- Impact of swift heavy ion on devices, in collaboration with Dr. Rongming Chu
- Local strain near surfaces and interfaces, in collaboration with Dr. Reeja Jayan

Thank you!

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